

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :  
Yoshikazu Nagamura, et al. :  
Serial No.: :  
(Divisional of Serial No. 09/504,728) : Group Art Unit:  
Filed: February 09, 2001 : Examiner:  
For: METHOD OF AND APPARATUS FOR WASHING PHOTOMASK AND WASHING  
SOLUTION FOR PHOTOMASK

PRELIMINARY AMENDMENT

Commissioner for Patents  
Washington, DC 20231

Sir:

Prior to examination of the above-referenced application, please amend the application as follows:

## IN THE CLAIMS:

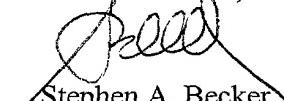
Claim 6, line 2, change "also employing ultrasonics waves in said first step of claim 1" to  
--wherein said step of removing organic matter and metal impurities employs ultrasonics waves--

## REMARKS

Entry of this preliminary amendment is respectfully requested.

Respectfully submitted,

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